

# Tackling Energy Challenges: Can Nano Help?

Nano for the sake of Nano  
versus  
Nano for making an impact “in time”

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National Taiwan University

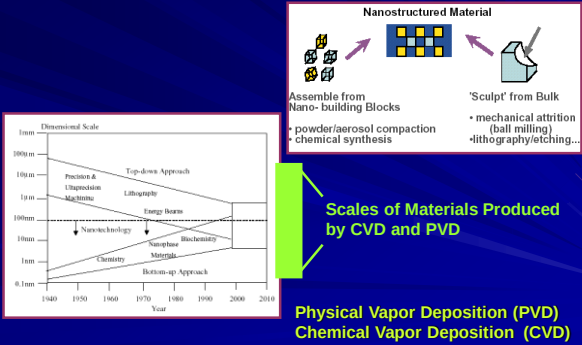
## Motivation

Green & Miniaturized Products

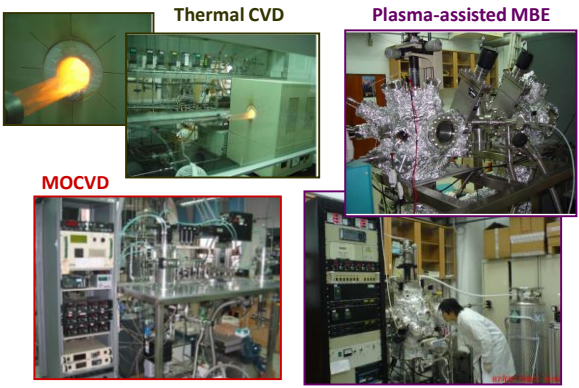
Nano-materials for Energy Applications



## Processes of Nano-materials: Bottom-up vs. Top-down Approaches



## Modern Alchemy (I)



## Core Process Techniques at CCMS-AML

- Microwave plasma
- Electron-cyclotron-resonance plasma
- Thermal- and MO-CVD
- Inductively Coupled Plasma

### CVD

Gas phase reaction, Gas-solid interaction  
Formation kinetics

- Magnetron sputtering
- Ion beam sputtering
- Atom- and Ion-beam assisted PVD
- Molecular beam epitaxy

### PVD

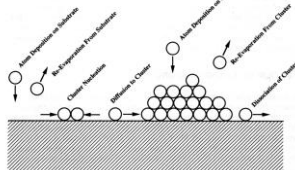
Hydrogen vs. H-free growth environments  
Film formation via physical route (varying K.E.) vs. chemical route (reactive sputtering)

Highly energized vapor deposition/etching processes  
under situations far away from equilibrium

## Gas Phase Syntheses

- Evaporation-Condensation (Earliest methods)
- Sputtering
- Laser Ablation
- Arc Discharge
- Aerosol Process
- Spray Pyrolysis
- Plasma Spray

atomic process in the nucleation of  
three-dimensional clusters of  
deposited film atoms on a substrate



(J. S. Horowitz and J. A. Sprague, Chap. 8, Pulsed Laser Deposition of Thin Film, Eds., D. B. Chrisey and G. K. Hubler, Wiley Interscience)

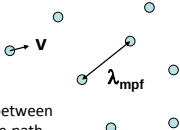
Gas Phase Pressure and Mean Free Path

$P = 1/3 n M v^2 / N_A$

Where  $N_A$  is Avogadro's number,  $v^2$  is mean square velocity,  $M$  the molecular weight and  $n$  is the number of molecules per unit volume.

$\lambda_{mpf} = 5 \times 10^{-3} / P$

The mean distance traveled by molecules between successive collisions is called the mean-free path.



Strong Function of Kinetic Energy or Temperature

Correlation between Gas Pressure and Other Film Formation Parameters

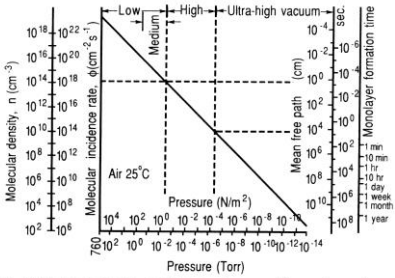
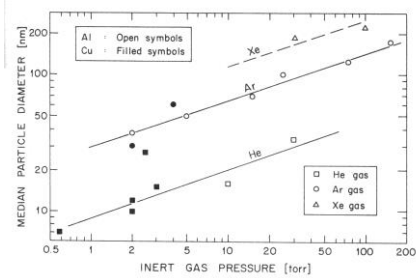


Figure 2-2. Molecular density, incidence rate, mean-free path, and monolayer formation time as a function of pressure. (Reprinted with permission from Ref. 2).

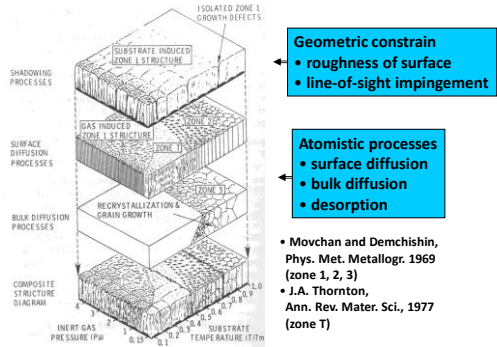
(A. Roth, Vacuum Technology, 1976)

Size Control of Clusters and Nanoparticles

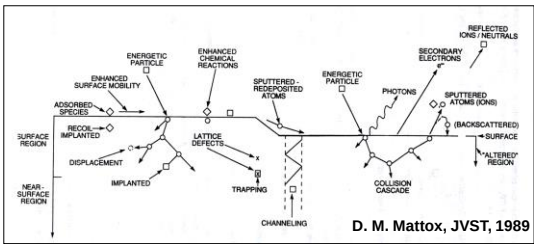


(C. G. Granqvist and R. A. Buhrman, JAP, 1976)

Structural Zones in Physical Processes: Fully-developed Grain Structures

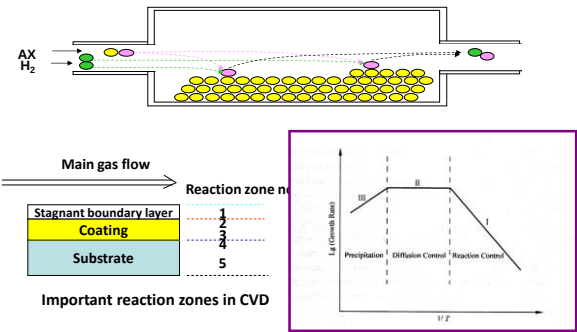


Ion-Surface Interaction



Applications: deposition, surface modification, implantation, etc.

Schematic of Chemical Vapor Deposition



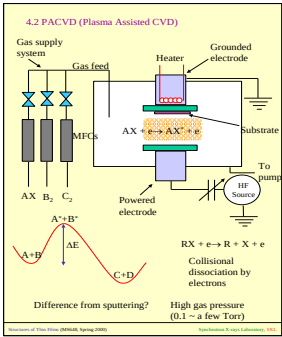
Common CVD Precursors

| Properties of common organometallic precursors for semiconductor growth. |                         |            |                               |                              |       |                                                                                      |
|--------------------------------------------------------------------------|-------------------------|------------|-------------------------------|------------------------------|-------|--------------------------------------------------------------------------------------|
| Element                                                                  | OM source               | Symbol     | Vapor pressure at 25°C (Torr) | Vapor pressure equation [17] |       | Comments                                                                             |
|                                                                          |                         |            |                               | A                            | B     |                                                                                      |
| Gallium                                                                  | Trimethylgallium        | TMGa, TMG  | 228.2                         | 1703                         | 8.07  | Most common Ga source, source of C in CBE                                            |
|                                                                          | Triethylgallium         | TEG, TEGa  | 5.9                           | 2322                         | 8.224 | Best source for high-purity source, low growth rates                                 |
|                                                                          | Triethylaluminum        | TMA        | 11.6                          | 2134.8                       | 8.224 | Most common aluminum source, high carbon incorporation                               |
| Aluminum                                                                 | Triethylaluminum        | TEA        | 0.03                          | 2361.2*                      | 8.999 | Very low vapor pressure, reduced C incorporation, parasitic reactions                |
|                                                                          | Tri-isobutyl aluminum   | TIBA       | 0.15                          | 1710.3*                      | 7.121 | Source for Al metal as well as Al alloys, possibly reduced C incorporation, unstable |
| Indium                                                                   | Trimethylamine          | TMAA       |                               |                              |       | Promising source for high-purity Al-containing materials, low vapor pressure         |
|                                                                          | Trimethylindium         | TMI        | 2.58                          | 3014                         | 10.52 | Most common indium source, source stability and reproducibility problems, solid      |
|                                                                          | Triethylindium          | TEI        | 0.31                          | 2815                         | 8.93  | Liquid indium source, low vapor pressure, pre-reaction problem                       |
| Arenic                                                                   | Ethylmethylindium       | EDMIn      | 3.2                           |                              |       | Promising alternative to TMIn, liquid, may not be thermally stable                   |
|                                                                          | Tertiarybutyl arsine    | TBA, TBAs  | 182.1                         | 1562.3                       | 7.5   | Liquid alternative to arsine, high-quality material, very expensive                  |
|                                                                          | Diethyl arsine          | DEAs       | 50.6                          | 1680                         | 7.339 | Liquid alternative to arsine, good-quality material, very expensive                  |
| Phosphorus                                                               | Trimethylarsine         | TMAAs      | 275                           | 1480                         | 7.405 | Poor alternative to arsine due to carbon incorporation, used as carbon doping source |
|                                                                          | Tertiarybutyl phosphine | TBP        | 265.7                         | 1339                         | 7.586 | Best liquid alternative to phosphine                                                 |
|                                                                          | Trimethyl antimony      | TMSAs      | 103.6                         | 1697                         | 7.707 | Relatively high decomposition temperature                                            |
| Zinc                                                                     | Diethylzinc             | DEZn, DEZs | 16.1                          | 2109                         | 8.28  | Zn doping source, also source for II-VI compounds                                    |
|                                                                          | Dimethylzinc            | DMZ, DMZs  | 365                           | 1560                         | 7.802 | Zn doping source, very high vapor pressure, source for II-VI compounds               |
|                                                                          | DEZn-amine              | DMZA       |                               |                              |       | Promising source for II-VI materials, resistant to pre-reaction with hydrides        |
| Iron                                                                     | Iron pentacarbonyl      |            | 35                            |                              |       | Source for semi-insulating InP                                                       |

\* Log P = B - A(T - 73.82).

\* Log P = B - A(T - 83.92).

Plasma-assisted CVD



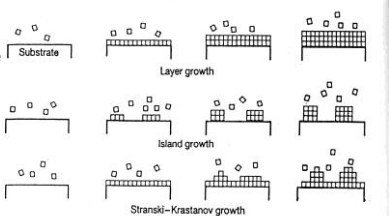
- Generation of plasma: DC, RF, Microwave, ECR
- Typical kinetic energy of electron ~ 1-10 eV, and ion ~ 0.02-0.1 eV
- Reduced activation energy

Nucleation and Growth of Films: The Three Conventional Modes

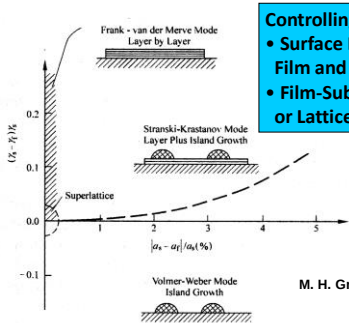
2-d full-monolayer  
Frank-van der Merwe

3-d (or "0-d") island  
Volmer-Weber

2-d and 3-d  
Stranski-Krastinov



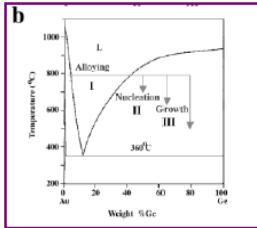
Selection of Growth Modes



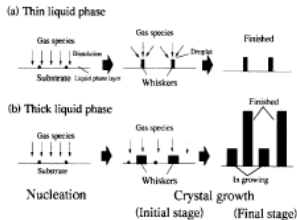
Controlling Parameters:  
• Surface Energies of both Film and Substrate  
• Film-Substrate Interface Energy or Lattice Mismatch

M. H. Grabow, et al, TMS, 1986.

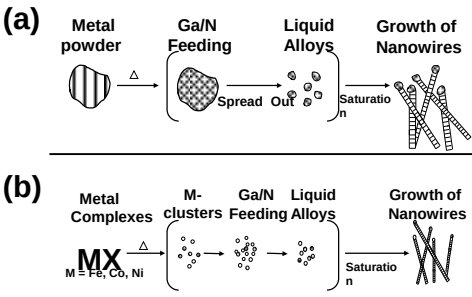
Vapor-Liquid-Solid Growth



Y. Wu and P. Yang, J. Am. Chem. Soc. 2001

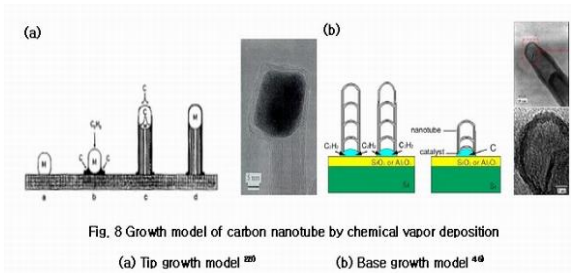


Introducing Catalyst via Different Pathways: Gaseous Source versus Solid/Liquid Source



C.-C. Chen et al., J. Am. Chem. Soc., 2001

Growth of CNT with Catalyst



C. H. Bartholomew

**The Nano-world at CCMS-AML:**  
**a Fruitful Research Field with Technology Implications**

**Wire/Rod**  
JACS 123, 2791 (2001)  
APL 81, 22 (2002)  
JACS 127, 2820 (2005)  
APL 88, 241905 (2006)  
APL 90, 213104 (2007)  
Adv. Func. Mater. 18, 938 (2008)  
Small 4, 925 (2008)  
Analytical Chem. 81, 36 (2009)  
J. Power Sources 195, 4418 (2010)  
Analytical Chem. 83, 1938 (2011)  
APL 79, 3179 (2001)  
APL 81, 4189 (2002)  
Adv. Func. Mater. 12, 687 (2002)  
APL 86, 203119 (2005)  
Chem. Mater. 17, 3749 (2005)  
JACS 128, 8368 (2006)  
PRB 75, 195429 (2007)  
JACS 130, 3543 (2008)  
Chapter 9, pp. 259-309  
Nanowires and nanobelts, Z.L. Wang Ed., Kluwer (2004)  
Adv. Func. Mater. 16, 537 (2006)  
APL 90, 123109 (2007)  
Adv. Mater. 19, 4524 (2007)  
Adv. Mater. 14, 1847 (2002)  
Nature Mater. 5, 102 (2006)  
APL 96, 263105 (2010)

**Tube**  
APL 82, 1420 (2003)  
Nano Lett. 4, 471 (2004)  
Chem. Mater. 17, 953 (2005)  
Adv. Func. Mater. 15, 783 (2005)  
APL 86, 203119 (2005)  
US Patent 6,860,528 B2  
APL 88, 143105 (2006)  
Nature Nanotech. 2, 170 (2007)  
Nano Lett. 9, 1839 (2009)  
Biosens. Bioelectron. 26, 2413 (2011)  
APL 81, 1312 (2002)  
Nano Lett. 3, 537 (2003)  
Adv. Func. Mater. 14, 233 (2004)

**Nanotip**  
Thin Films and Composites:  
APL 86, 21911 (2006)  
APL 86, 83104 (2006)  
APL 86, 161901 (2005)  
APL 87, 261915 (2005)  
JST B 24, 97 (2006)  
APL 88, 73515 (2006)  
Adv. Mater. 21, 759 (2009)  
Chem. Comm. 47, 9414 (2011)  
Carbon 49, 4911 (2011)  
ACS Nano 5, 6564 (2011)

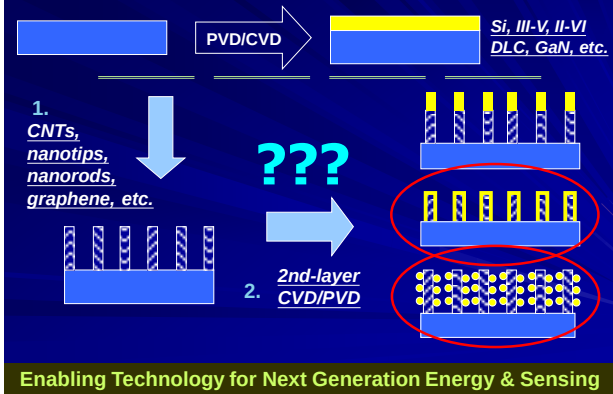
**Core-shell**  
APL 81, 1312 (2002)  
Nano Lett. 3, 537 (2003)  
Adv. Func. Mater. 14, 233 (2004)

**Belt**  
APL 81, 1312 (2002)  
Nano Lett. 3, 537 (2003)  
Adv. Func. Mater. 14, 233 (2004)

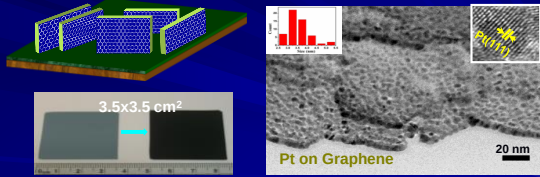
**Peapod**  
APL 81, 1312 (2002)  
Nano Lett. 3, 537 (2003)  
Adv. Func. Mater. 14, 233 (2004)

**Brush**  
APL 81, 1312 (2002)  
Nano Lett. 3, 537 (2003)  
Adv. Func. Mater. 14, 233 (2004)

The Modern Alchemy (II)



Arrayed Graphene and Carbon Nanotubes:  
On-chip Synthesis, Electrochemical Properties for  
Energy and Sensing Applications

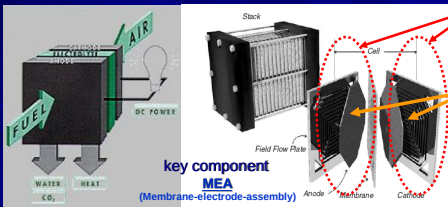


Outline

- Quest of next-generation energy solution
  - Why graphene and CNT? How they can help?
- On-chip, direct-growth of graphene and CNT
  - Evidence of strain in few-layer graphene
  - Deposition of Pt on graphene and CNT
- Electrochemical properties
  - Charge transfer between Pt and graphene
- Supercapacitor and fuel cell
- Others: sensor, transparent conduction film

CNTs or Graphene for Energy Applications

- Green and miniaturized products:
  - power for portable electronics
- Integrated material/device design:
  - enhanced electrochemical properties
  - novel micro energy devices





### Cost Issue for Electro-catalyst

**Cost of Fuel Cells (PEMFCs)**

Total: Pt-180g, Ru-45g (47% of MEA cost)

**5 Year Platinum**

~ 50 millions cars in 2010 = 90,000 tons of Pt  
Total Pt in the world ~ 28,000t!

H. Gasteiger et al. Appl. Catal. B: Environ. 56 (2005) 9  
X. Yu, Journal of Power Sources 172 (2007) 133

**R & D goals**

- Improving Efficiency in the Usage of Pt & Ru
- Searching for Non-precious Metal Catalysts

### Amazing Carbons: from $sp^3$ to $sp^2$ and $sp$

Graphene: 2D Building Block for Graphitic Materials

Single-  
↓  
Double-  
↓  
Multi-layer,  
↓  
Graphite  
(N>>?)

The extended family of  $sp^2$  C

K. S. Novoselov et al., Science 306 (2004) 666  
A. K. Geim et al., Nature Mater. 6 (2007) 183

**Nobel Prize in Physics**

### Band-gap Engineering of Graphene

I. Nanoribbon: Confinement effect & Edge effect

$E_{gap} = \alpha / (W - W^*)$

(a) 3D schematic of graphene nanoribbons on metal electrodes (Cr/Au).

- Mechanical exfoliated graphene
- Width (W): 10-100 nm, Length: 1-2  $\mu$ m
- Temp.-dependent Conductance

M.Y. Han et al., PRL 98 (2007) 206805

II. Graphene/SiC: Substrate-induced band-gap opening

ARPES: Angle-resolved Photoemission Spectroscopy †  
S. Y. Zhou et al., Nature Mater. 6 (2007) 770, E. Rotenberg et al., Nature Mater. 7 (2008) 258

$N > 4, \Delta = 0$

### Band-gap Engineering of Graphene (continued)

III. In-situ co-doping of B/N to graphene

(a) XPS spectra of Graphene, G-BN(1 at. %), G-BN(2 at. %), and G-BN(4 at. %).

(d) Schematic of increasing BN concentration in graphene.

> XES-XAS studies reveal  $\pi-\pi^*$  band opening in graphene with increasing BN concentration in low concentration regime

> A significant band gap of around 0.6 eV is observed for 6BNB (6% BN) films

ACS Nano 7 (2013) 1333

### Orientation Controlled Growth?

- Let graphene stand up!

• Exfoliation routes  
• Epitaxial growth

**New synthetic route?**

- Large-scale
- Contaminant-free

### CNTs Grown by Microwave-CVD

AsTex, 1.5 kW

Adv. Func. Mater. 12 (2002) 687

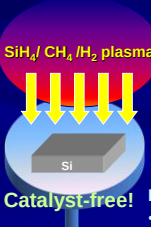
- ✓CNT Diameter : Catalyst Particle Size
- ✓CNT Length : Deposition Time/Temp.
- ✓Direct Growth on Patterned Si, Glass or Metal Substrates

### Orientation-controlled Growth of Graphene: a Chip Process

**Microwave Plasma CVD (MWCVD)**



**SiH<sub>4</sub>/CH<sub>4</sub>/H<sub>2</sub> plasma**



**Catalyst-free!**

**Graphene (edge-oriented)**



3.5x3.5 cm<sup>2</sup>

Si

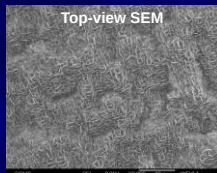
SiC

Key factors on phase/structure

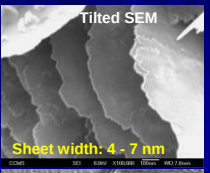
- Polytype control of SiC
- Interface of SiC-buffer/Si, SiC@Graphene/SiC-buffer
- Epitaxy/orientation relationship
- Density & size control

Microwave power : 1000-2000 W  
Growth temperature : 900-1100 °C  
Pressure: 60-80 Torr  
SiH<sub>4</sub>: 1-4; CH<sub>4</sub>: 5-20; H<sub>2</sub>: 50-400 sccm

### Wafer-Scale Production of Edge-Oriented Few-layer Graphene (FLG)

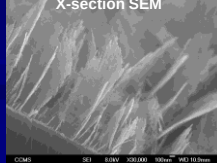


Top-view SEM

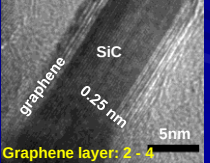


Tilted SEM

Sheet width: 4 - 7 nm



X-section SEM



HRTEM

graphene

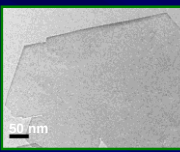
SiC

0.25 nm

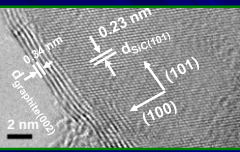
5nm

Graphene layer: 2 - 4

### Graphene-SiC Heterojunction



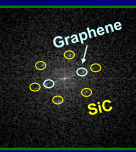
50 nm



0.23 nm

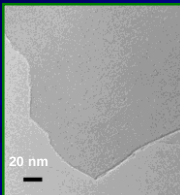
0.25 nm

(2-4 graphitic layer)

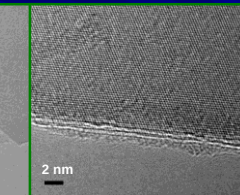


Graphene

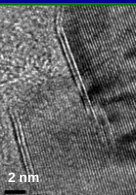
SiC



20 nm

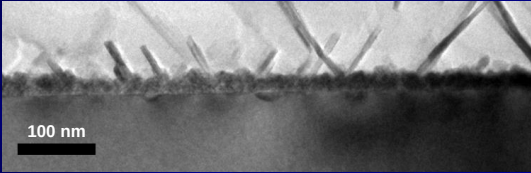


2 nm

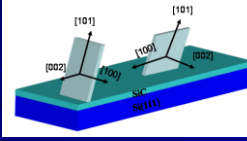


2 nm

### Orientation/Epitaxy Relationship of Edge-Oriented FLG and Si Substrate



100 nm



[101]

[002]

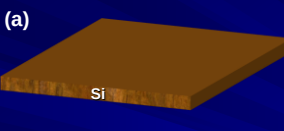
[101]

[002]

0.23 nm

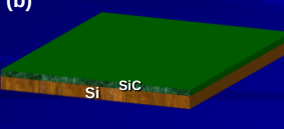
0.25 nm

### Schematic of Edge-Oriented FLG Growth



(a)

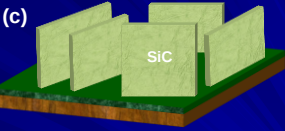
Si



(b)

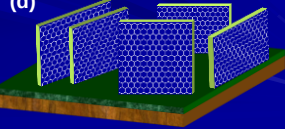
Si

SiC



(c)

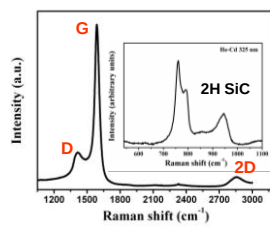
SiC



(d)

### Raman Spectrum of Edge-Oriented FLG

**Present work: edge-oriented FLG**



Intensity (a.u.)

Raman shift (cm<sup>-1</sup>)

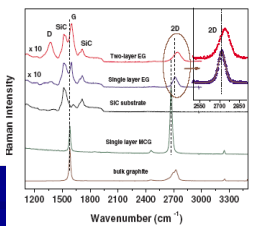
G

D

2H SiC

2D

**Epi-Graphene on SiC**



Raman intensity

Wavenumber (cm<sup>-1</sup>)

Single layer EG

SiC substrate

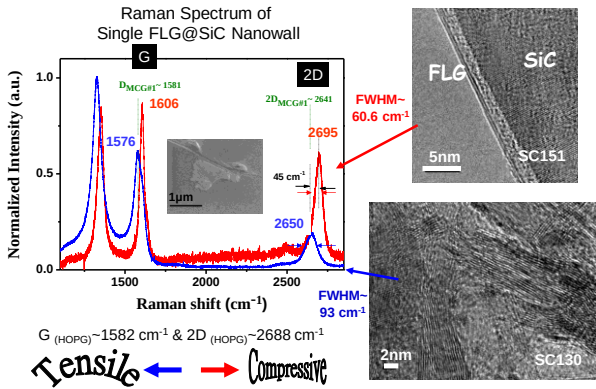
Single layer MG

bulk graphite

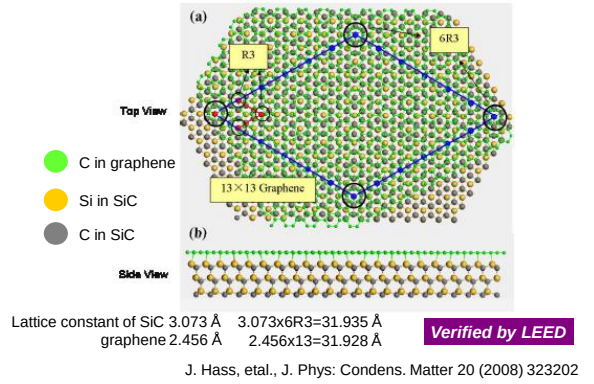
**Interaction of SiC and FLG: Peak shift & broadening Occurrence of D band**

Z. H. Ni et al., PRB 77 (2008) 115416

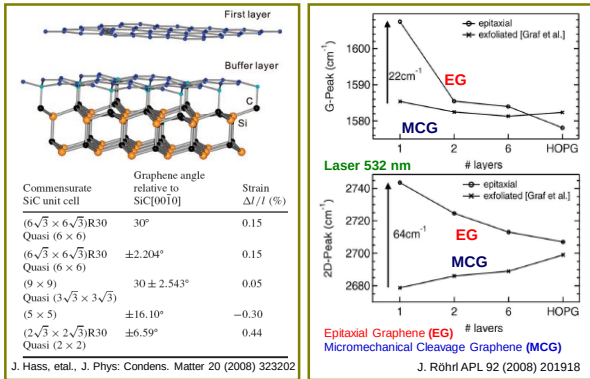
Presence of Strain in Few-layer Graphene



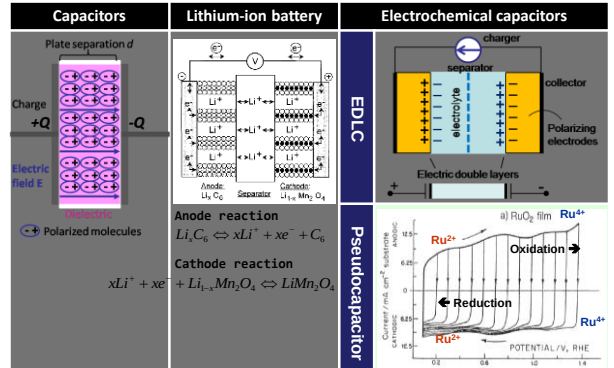
Epitaxial Graphene on SiC: Commensurate Structure



Epitaxial Graphene on SiC: Strain & Phonon Hardening



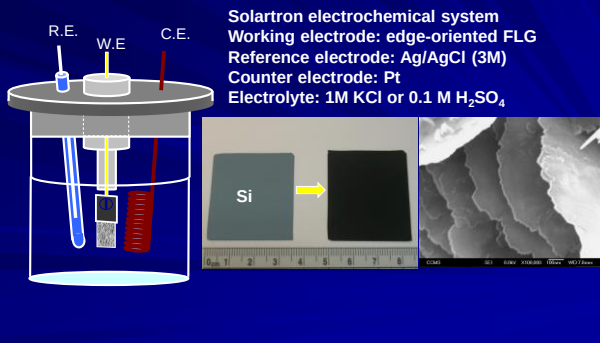
Energy Storage: Basics



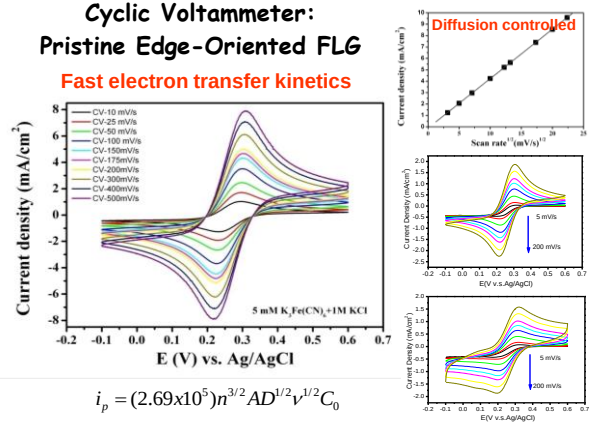
Wolfgang H. Meyer Adv. Mater. (1998) 10, No. 6 439

M Jayalakshmi, K Balasubramanian Int. J. Electrochem. Sci., 3 (2008) 1196

Electrochemical Measurements



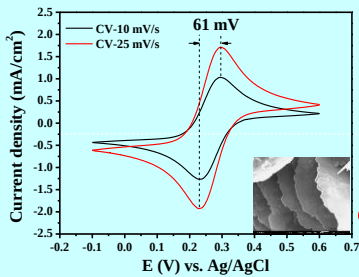
Cyclic Voltammeter:  
Pristine Edge-Oriented FLG  
Fast electron transfer kinetics





Nearly Ideal Electron Transfer Kinetics

CV of edge-oriented FLG: Nerstian Behavior  
One-electron Transfer & Reversible Process

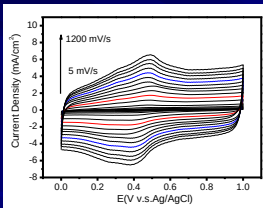


| Electrode                    | $\Delta E_p$ (mV) |
|------------------------------|-------------------|
| Pt                           | 88                |
| CNTs                         | 59                |
| Basal plane                  | >700              |
| HOPG                         | 70                |
| Edge plane                   | 70                |
| HOPG                         | 70                |
| Edge-oriented FLG (our work) | 61                |

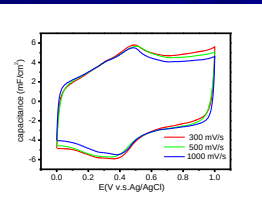
HOPG (highly ordered pyrolytic graphite)  
J.M. Nugent et al., Nano Lett. 1 (2001) 87

Capacitive Properties  
(Double-layer, non-Faradaic)

Cyclic Voltammograms  
in 1M H<sub>2</sub>SO<sub>4</sub> Solution

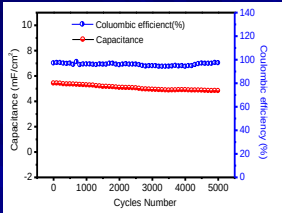
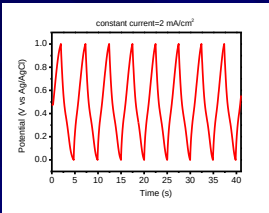


Capacitance–Voltage Curves



- Scan rate can be up to 1200 mV/s.
- With aqueous-based supercapacitors, it is generally limited to around 1V, due to water electrolysis.

Galvanostatic Charge/Discharge Analyses

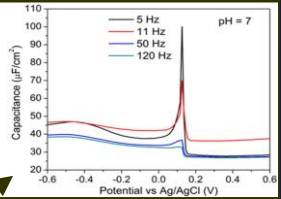
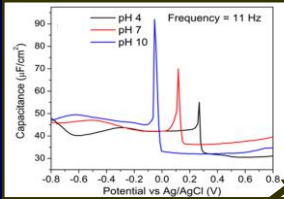


$$C_p = \frac{I}{a(dV/dt)} = 5.15 \text{ mF/cm}^2$$

Electrolyte: 1 M H<sub>2</sub>SO<sub>4</sub> solution  
Potential = 0.0 V ~ 1.0 V  
Constant current = 2.0 mA/cm<sup>2</sup>

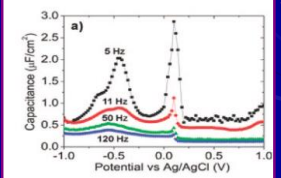
$$\frac{C_{\text{discharge}}}{C_{\text{charge}}} = \text{Coulombic efficiency (\%)}$$

Edge-oriented FLG-array vs. Planar FLG



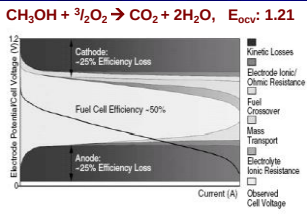
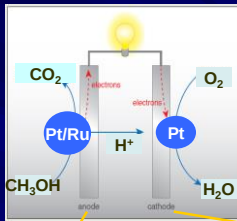
30-fold Increase in  
Peak Capacitance!  
Edge-oriented FLG:  
100μF/cm<sup>2</sup> (5Hz)

Planar-FLG:  
3μF/cm<sup>2</sup> (5Hz)



Graphene (or CNT)-Pt Composite  
as  
Electro-Catalyst for Fuel Cell

Membrane Electrode Assembly in DMFC



Anode Challenges:

- Poor catalytic kinetics
- Catalyst poisoned
- Catalyst agglomerated
- Catalyst inactive (Ru → RuO<sub>x</sub>)
- CO<sub>2</sub> stuck

Cathode Challenges:

- Poor catalytic kinetics
- Catalyst agglomerated
- Methanol crossover
- Flooding
- Support corrosion



### Issues for Electro-catalyst

Fuel

Diffusion layer

Electro-catalyst layer

$H^+/H_2O$

#### Tri-phase Junction

Fuel

$H_2O$

$H^+$

membrane

GDL

membrane

- Carbon
- Active Pt
- Unused Pt
- Ionomer
- Nafion® (Dupont)

Pt on Vulcan XC 72R

100 nm

Pt on Mesoporous Carbon

25 nm

### Carrier Pathways

#### Bumpy Road

Conventional process

#### Expressway

New approach: Direct growth

### Nanoscale Heterojunctions: Interface Physics and Chemistry

Interface 2: CNTs/Graphene and catalyst

Interface 3: CNTs/Graphene and back-electrode

Interface 1: Catalyst-electrolyte

Choices of back-electrode

- CNTs on carbon cloth
- CNTs on Si wafer
- Ti (or  $TiSi_x$ ) buffer layer: adhesive & conductive

J. Vac. Sci. Tech. B 24 (2006) 87 & Electrochemical and Solid State Lett. 9 (2006) A175

### Deposition of Pt on CNT or Graphene: Where Does Pt Want to Sit?

(I) Chemical Effect: *accepter versus donor*

N-doped

B-doped

(With permission from C. W. Chen, Dept. of Mater. Sci., NTU)

(II) Strain Effect: *inward versus outward charge transfer*

How the strain in graphene affects nucleation, growth and diffusion of Pt?

### Well-dispersed Pt/Ru NP on $CN_xNT$ : Excellent Electro-catalysts for Proton Exchange Membrane Fuel Cell

2 nm

Outer shell

Highly-coordinated N in graphene

Inner nodes Pyridine-like N

20 nm

2 nm

Chemistry of Materials 17 (2005) 3749

### Next-generation Energy Solution (I): Fuel Cell with Low-loading of Precious Metals

Ultrafine Pt/Ru Nanoparticles Uniformly Dispersed on Arrayed Carbon Nanotubes with High Electrochemical Activity at Low Loading of Precious Metal

Chemistry of Materials 17 (2005) 3749 & J. Power Sources 171 (2007) 55 [both are highly-cited papers]

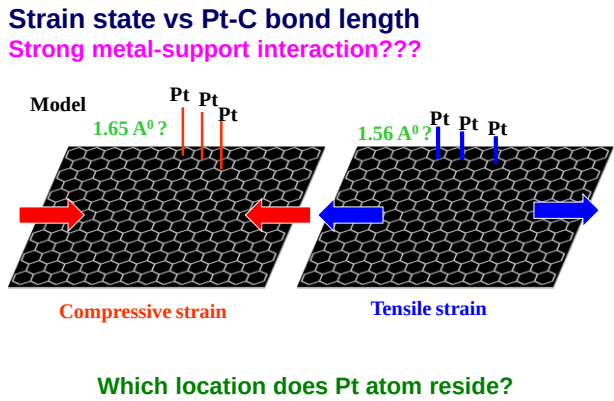
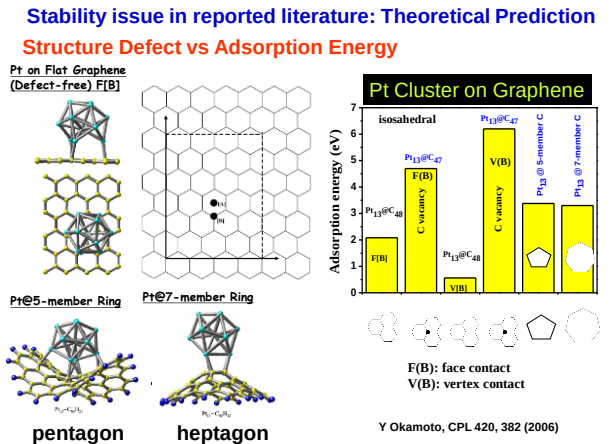
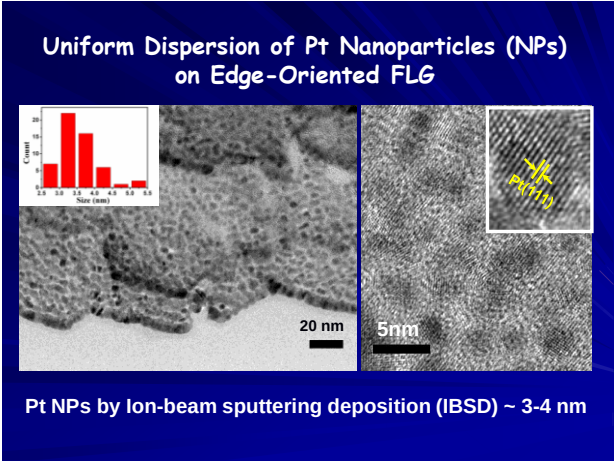
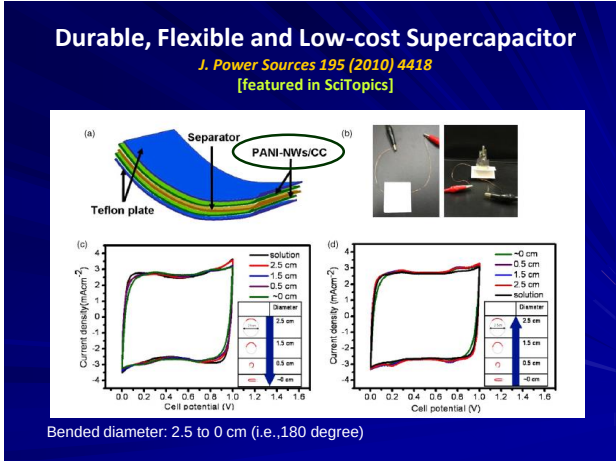
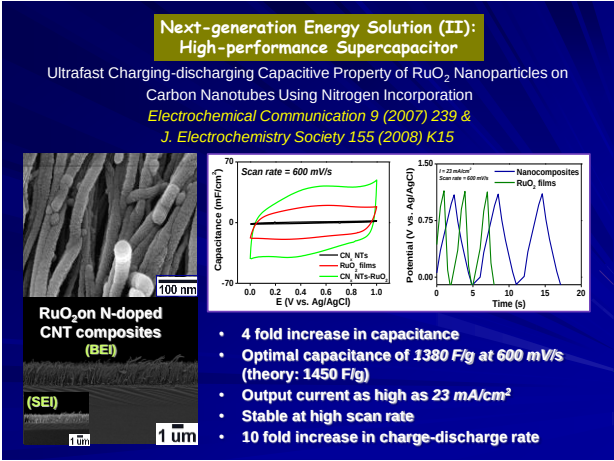
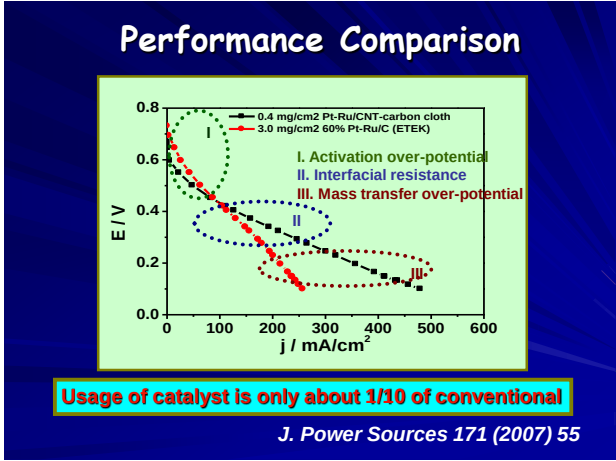
2 nm

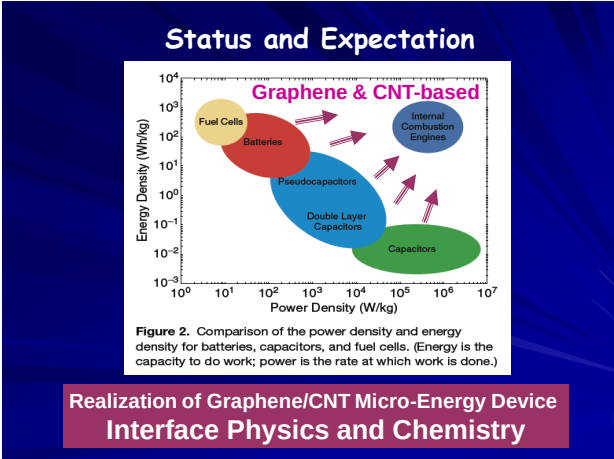
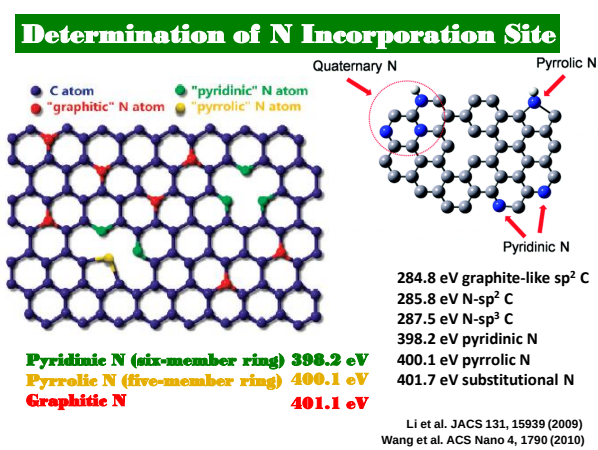
Pt on Nitrogen-doped CNT

P / mW/cm<sup>2</sup>

j / mA/cm<sup>2</sup>

- Only **one tenth** of metal loading, in comparison to the conventional, is needed.
- NEXT: Shape-controlled Pt/Ru NPs, stability/durability, etc.
- How about Pt/Ru on graphene?





### Summary (I)

- Large-scale synthesis and edge-oriented growth of multi-layer graphene (FLG, N=2-4)
- Presence of strain may be advantageous
- Superior electron transfer kinetics ( $\Delta E_p \sim 61$  mV)
- On-chip direct growth of metal catalyst onto FLG shows uniform dispersion of nanoparticle ( $\sim 3-4$  nm) with enhanced forward to reverse current ratio ( $> 2$ )
- Ultra-fast (up to 1200 mV/s) charging-discharging capacitive property and high Coulomb efficiency

Si

20 nm

## Solar to Fuel Generation

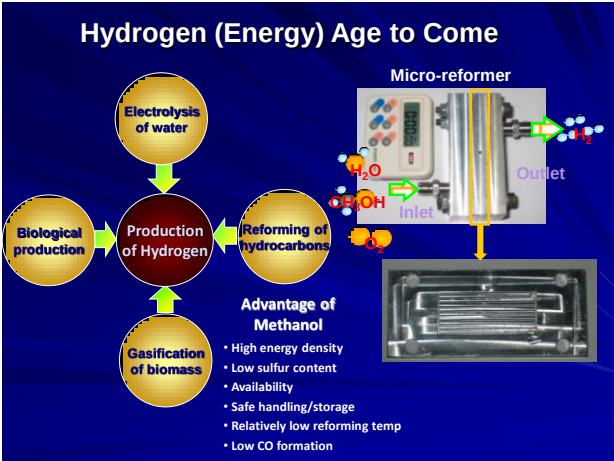
*We seek as a "Holy Grail" a renewable energy source driven by solar energy that produce a clean and storable fuel....*

- By Allen J. Bard and Marye Anne Fox, Acc. Chem. Res. 28 (1995) 141

- Hydrogen, the purest and zero carbon emission
- Hydrocarbons with low carbon to hydrogen ratio

## Outline

- Why hydrogen economy?
- What matters?
  - Choices of materials
  - Choice of fuels or electrolytes
  - Nano enhancement
  - Surface/Interface effect
  - etc. ....
- Case studies
  - ZnO-, GaN-nanorods based
  - Graphene oxides and hybrids





Challenge of Hydrogen Source

Liquid Fuel vs Hydrogen Bottles

48 hours of operation at 5 KW is either :

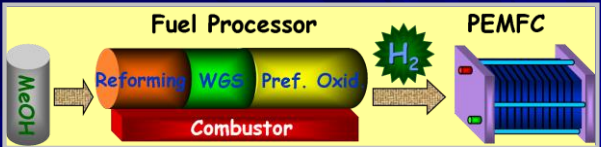


or



Fuel Processor with 55 Gallons of Methanol/Water Mixture

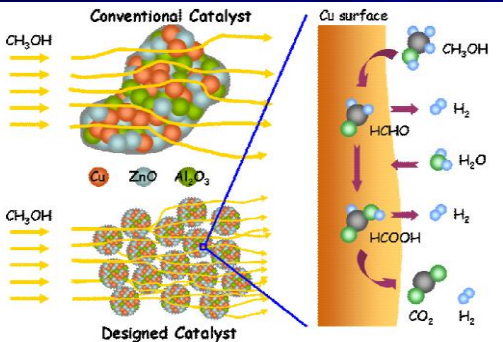
Reformed Methanol Fuel Cell Systems



Reforming Reaction :

- Steam Reforming of Methanol  
 $\text{CH}_3\text{OH} + \text{H}_2\text{O} \rightarrow \text{CO}_2 + 3\text{H}_2 \quad \Delta H_0 = +49.4 \text{ kJ/mol}$  [Endothermic]
- Partial Oxidation of Methanol  
 $\text{CH}_3\text{OH} + 1/2\text{O}_2 \rightarrow \text{CO}_2 + 2\text{H}_2 \quad \Delta H_0 = -192.2 \text{ kJ/mol}$  [Exothermic]
- Oxidative Steam Reforming of Methanol (Autothermal Reforming)  
 $\text{CH}_3\text{OH} + a \text{O}_2 + b \text{H}_2\text{O} \rightarrow \text{CO}_2 + (4a+3b)\text{H}_2 \quad \Delta H_0 \sim 0 \text{ kJ/mol}$

Gas Reforming for  $\text{H}_2$

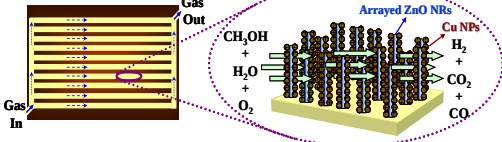


ISEF Young Scientist Award 2008

Next-generation High-efficiency Reformers for  $\text{H}_2$ -production with Low CO Emission

Nanostructured  $\text{ZnO@Cu}$  as Catalyst for Microreformers  
Y. G. Lin, et al., Angew. Chem. Int. Ed. 48, 7586-7590 (2009)

Microchannel Reactor



Superb catalytic performance of the Cu NP-decorated ZnO NR nanostructures for methanol reforming in a microreformer has been reported. The breakthrough can be to the larger surface area and enhanced dispersion of fine Cu NPs, formation of microstrain, the modification of electronic structure of Cu species, and the existence of strong metal-support interaction effect. These results present new opportunities in the development of highly active and selective NR@NP nanoarchitectures for a wide range of catalytic reaction systems.

Low-Cost Process of ZnO Nanorods with Cu Nanoparticles as Micro-reformation Catalysts

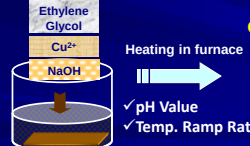
1st step



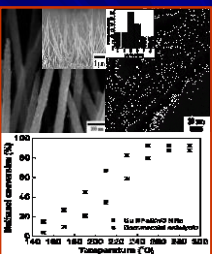
Arrayed ZnO NRs



2nd step



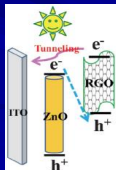
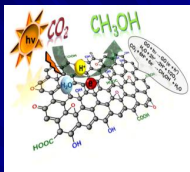
Cu NPs/ZnO NRs



Chen et al., Angew. Chem. Int. Ed. 48, 7586 (2009)

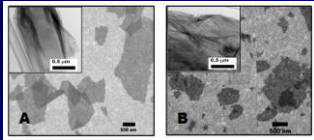
Graphene Oxide with Tunable Oxidation Level for Photo-Chemical Applications

- Tuning the oxidation level and bandgap:  
Modified Hummer's method & Electrochemical method
- Solar-to-fuel:  
Photo-catalytic conversion of  $\text{CO}_2$  & Photo-electrochemical (water-splitting)
- Hybrids:  
- GO mixed w/ $\text{MoS}_2$  or Cu NPs (as sensitizer or co-catalyst)  
- rGO (as sensitizer) coated ZnO  
etc.



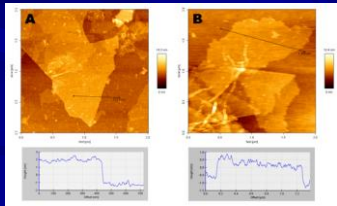


### Morphology: SEM and AFM



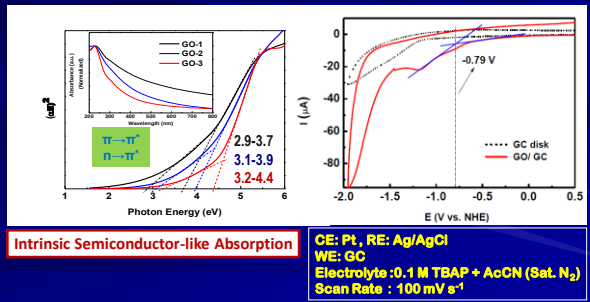
Wrinkled paper like morphology from phenolic and epoxy functional groups on the basal plane

Lateral dimensions of several micrometers and a thickness of 1-3 nm



Nanoscale, 2013, 5, 262-268

### Band Gap and Conduction Band Position of Graphene Oxide

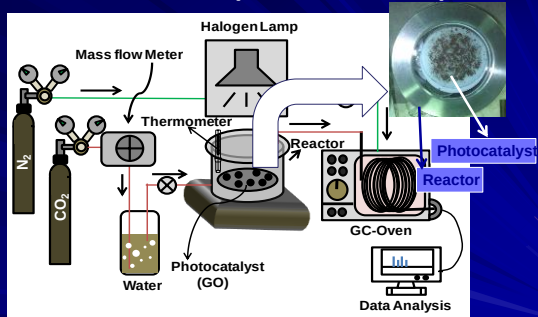


Intrinsic Semiconductor-like Absorption

CE: Pt, RE: Ag/AgCl  
WE: GC  
Electrolyte: 0.1 M TBAP + AcCN (Sat. N<sub>2</sub>)  
Scan Rate : 100 mV s<sup>-1</sup>

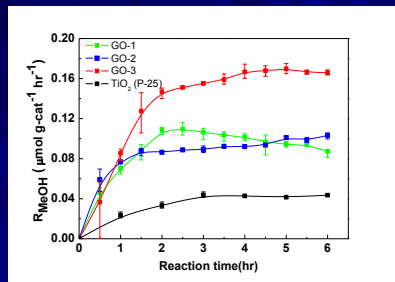
Nanoscale, 2013, 5, 262-268

### Solar-to-Fuel Experimental Setup



Before reaction:  
1. Purging N<sub>2</sub> for 1h, and then CO<sub>2</sub> for 1h.  
2. Exp. conditions:  
Flow rate: 4 ml/min(Continuous flow reaction)  
Light source: ELH, Reaction temperature: 30 °C

### CO<sub>2</sub> to Methanol Conversion



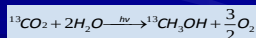
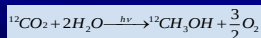
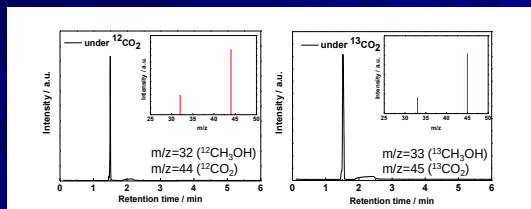
Methanol formation rate 6 times higher than TiO<sub>2</sub>

But, is this real?

Nanoscale, 2013, 5, 262-268

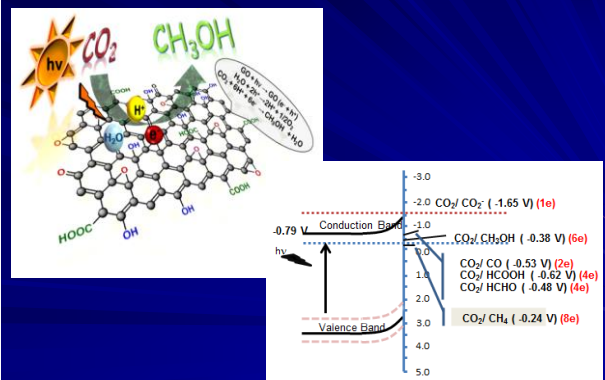
### Isotope Tracer Analysis:

direct evidence of the GO as effective photocatalyst



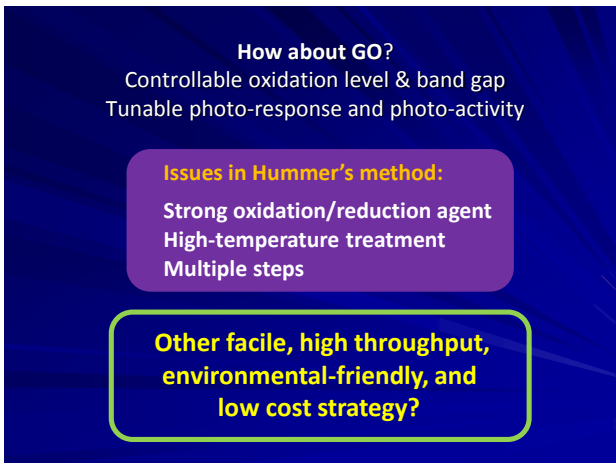
Nanoscale, 2013, 5, 262-268

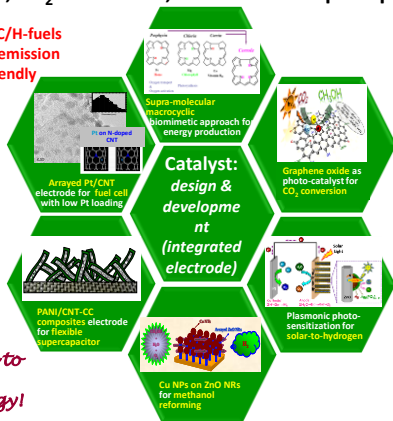
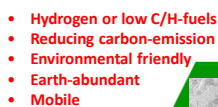
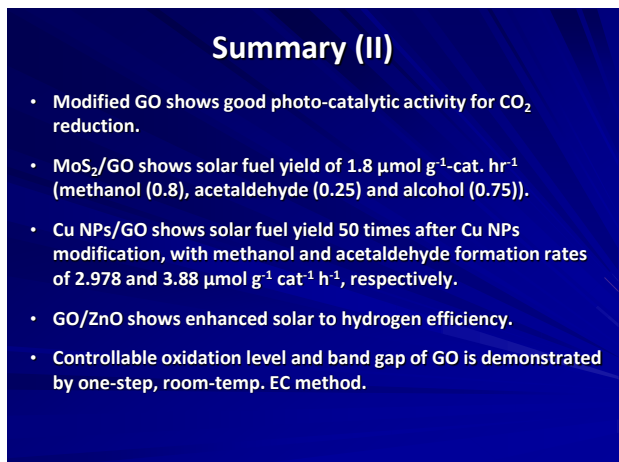
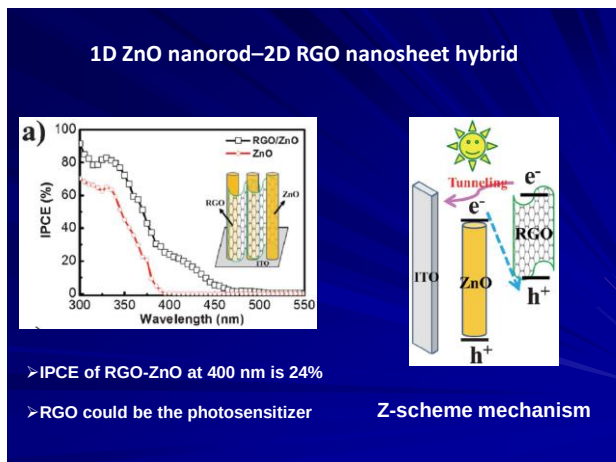
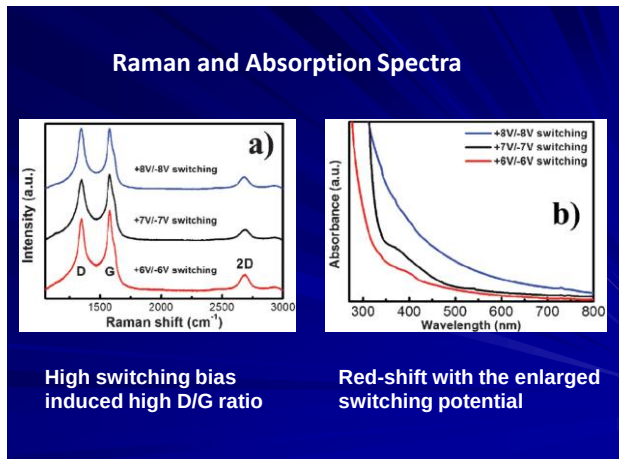
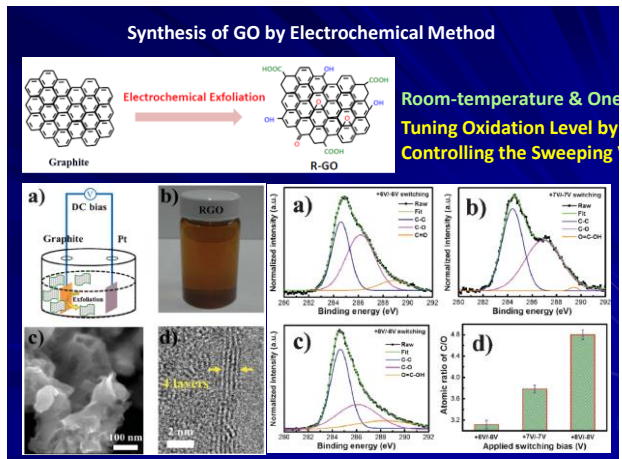
### Schematic CO<sub>2</sub> Reduction Mechanism on GO



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*A fruitful field to explore with nanotechnology!*

